

METHOD AND APPARATUS FOR INSPECTING A SUBSTRATE

ABSTRACT

In a method and an apparatus for inspecting defects on a substrate using a light beam,
5 a light source irradiates light beams having different wavelengths onto the substrate. A
detector detects first lights scattered from a surface of the substrate and second lights
scattered from impurities on the substrate by irradiation of the light beams. An operation unit
compares first intensities of the first lights with second intensities of the second lights in
order to produce differential values therebetween, and selects a wavelength corresponding to
10 a maximum value of the differential values. An inspection process for inspecting the defects
on the substrate is performed using a light beam having the selected wavelength.